

Notice of References Cited	Application/Control No. 10/782,821		Applicant(s)/Patent Under Reexamination FUTATSUYA ET AL.	
	Examiner Russ Guill		Art Unit 2123	Page 1 of 3

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*	B	US-5,278,421	01-1994	Yoda et al.	250/492.22
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	M	US-			

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*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kimitoshi Takahashi et al.; "Proximity effect correction using pattern shape modification and area density map", 2000, Journal of Vacuum Science and Technology B, Volume 18, Number 6, pages 3150 - 3157
	V	Bruno La Fontaine et al.; "Analysis of Flare and its Impact on Low-k1 KrF and ArF Lithography", 2002, Proceedings of the SPIE, Volume 4691, pages 44 - 56
	W	Andreas Erdmann et al.; "Enhancements in Rigorous Simulation of Light Diffraction from Phase Shift Masks", 2002, Proceedings of SPIE, Volume 4691, pages 1156 - 1167
	X	Chris A. Mack; "Measuring and Modeling Flare in Optical Lithography", June 2003, Optical Microlithography XVI, Proceedings of the SPIE, Volume 5040, pp. 151-161

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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	U	Y. C. Pati et al.; "Exploiting Structure in Fast Aerial Image Computation for Integrated Circuit Patterns", 1997, IEEE Transactions on Semiconductor Manufacturing, Volume 10, Number 1, pages 62 – 74
	V	Teruyoshi Yao et al.; "Local Flare Effects and Correction in ArF Lithography", June 2003, 2003 Symposium on VLSI Technology Digest of Technical Papers, pages 43 – 44
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	X	Joseph P. Kirk; "Scattered light in photolithographic lenses", 1994, Proceedings of SPIE, Volume 2197, pages 566 – 572

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